

شبكة المعلومات الجامعية







شبكة المعلومات الجامعية التوثيق الالكتروني والميكروفيلم



شبكة المعلومات الجامعية

جامعة عين شمس

التوثيق الالكتروني والميكروفيلم

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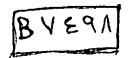
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Ain Shams University
Faculty of Girls
For
Arts, Science and Education



STRUCTURE AND PHYSICAL PROPERTIES OF CADMIUM GALOSELENIDE FILMS AND THE OPTIMUM CONDITIONS FOR SUITABLE ELECTRONIC APPLICATIONS

A Thesis

Submitted For The Ph.D. Degree of Philosophy In Science (Physics)

Ву

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